

17 July 2003

SciFinder

Page

Answer 1:

Bibliographic Information

Positive-type photoresist composition with low toxicity. Yoshimoto, Hiroshi; Suzuki, Nobuo. (Fuji Photo Film Co., Ltd., Japan). J Kokai Tokkyo Koho (1997), 13 pp. CODEN: JKXXAF JP 09244231 A2 19970919 Heisei. Patent written in Japanese.
Application: IP 96-52008 19960308 CAN 127-301274 AN 1997-619206 CAPLIS (Copyright 2003 ACS)

Patent Family Information

| Patent No | Kind | Date | Application No | Date |
|-------------|------|----------|----------------|----------|
| JP 09244231 | A2 | 19970919 | IP 1996-52008 | 19960308 |

Priority Application

| | |
|---------------|----------|
| IP 1996-52008 | 19960308 |
|---------------|----------|

Abstract

The compn. has (A) an alk.-sol. resin, (B) 1,2-naphthoquinonediazide-4-sulfonate and/or 1,2-naphthoquinonediazide-5-sulfonate, and (C) alkoxybutylacetate and/or alkoxypropylacetate. The compn. is useful for manufg. a semiconductor device, a liq. crystal, a printed circuit board etc. The compn. shows low toxicity, storage stability, good application property, high resolu., low striation, and heat resistance.

Patent Classifications

Main IPC: G03F007-004 **Secondary IPC:** G03F007-022; H01L021-027

Indexing -- Section 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Retrographic Processes)

Phenolic resins: uses

Role: DEV (Device component use); USES (Uses)

(novolac: pos.-type photoresist compn. contg. alkoxybutylacetate and/or alkoxypropylacetate with low toxicity)

Photoresists

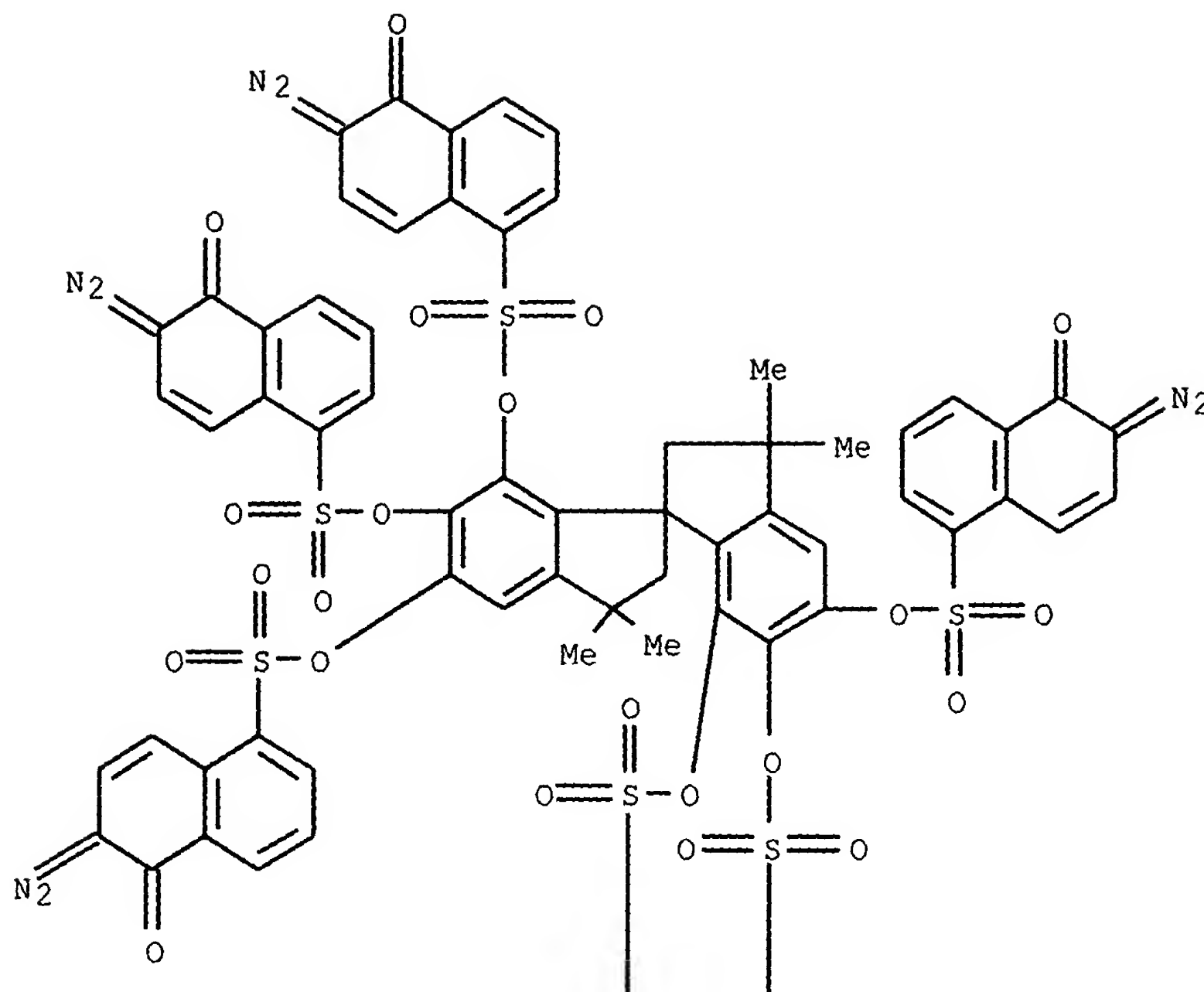
(pos.-type: pos.-type photoresist compn. contg. alkoxybutylacetate and/or alkoxypropylacetate with low toxicity)

68510-03-0

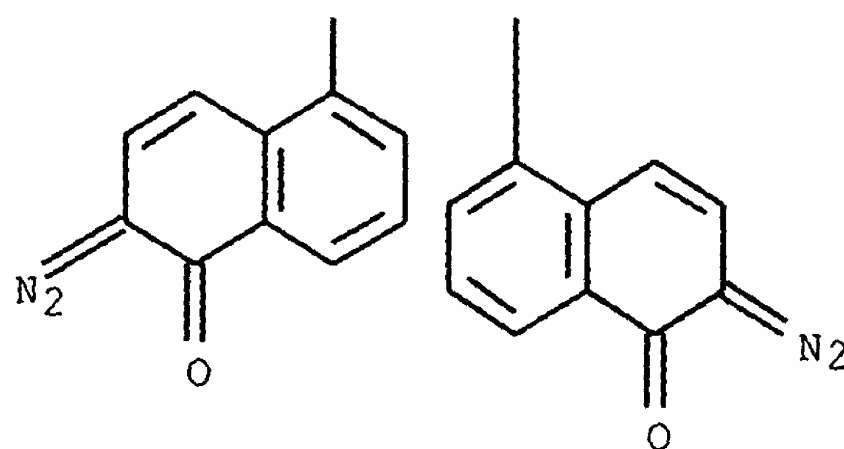
107761-81-9 2,3,4,4'-Tetrahydroxybenzophenone, 1,2-naphthoquinonediazide-5-sulfonate

136830-28-9

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143213-15-4

168634-43-3

197220-63-6

197220-66-9

Role: DEV (Device component use); USES (Uses)

(pos.-type photoresist compn. contg. alkoxybutylacetate and/or alkoxypropylacetate with low toxicity)

27029-76-1P, m-Cresol-p-cresol-formaldehyde copolymer

Role: DEV (Device component use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)

(pos.-type photoresist compn. contg. alkoxybutylacetate and/or alkoxypropylacetate with low toxicity)

4435-53-4, 3-Methoxybutylacetate

103429-90-9, 3-Methoxy-3-methylbutylacetate

Role: DEV (Device component use); MOA (Modifier or additive use); USES (Uses)

(pos.-type photoresist compn. contg. alkoxybutylacetate and/or alkoxybutylacetate with low toxicity)

Supplementary Terms

photoresist pos type alkoxybutylacetate alkoxybutylacetate; naphthoquinonediazide sulfonate toxicity free photoresist